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1	1.	A method for manufacturing an electroplating article, said method		
2	comprising:			
3		a) applying a conformable mask to an article comprising a first substrate		
4	and a patterne	d resist disposed on said first substrate;		
5		b) contacting a second substrate to said conformable mask such that said		
6	conformable n	nask obtains a pattern complementary to said pattern of said resist;		
7		c) separating said first substrate from said conformable mask, said		
8	conformable mask remaining adhered to said article; and			
9		d) removing said resist.		
10	said ar	ticle being capable of electroplating a pattern of metal corresponding to the		
11	complement o	f said pattern of said conformable mask onto an electrode when said article is		
12	placed in conta	act with the electrode in the presence of an electrolyte solution and subjected to		
13	an electric field	d.		
1	2.	A method for manufacturing an electrodepositing article, said method		
2	comprising:			
3		a) providing a porous medium having a first surface;		
4		b) treating said porous medium to create one or more nonporous regions;		
5	A single ment of	c) /applying a film to said first surface of said porous medium;		
6		d) / patterning said film to create a patterned mask; and		
7		e) / removing at least a portion of said one or more nonporous regions,		
8	said art	igle being capable of electroplating a pattern of metal corresponding to the		
9	complement of	said pattern of said conformable mask onto an electrode when said article is		
10	placed in conta	ect with the electrode in the presence of an electrolyte solution and subjected to		
11	an electric felo	1 .		
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3. (New) A method of making a supported mask, comprising:
obtaining a first support;
forming a surface relief pattern on the first support;
applying a conformable material over the surface relief pattern;
pressing said conformable material using a second support and allowing the conformable material to solidify and to adhere said conformable material to said second support;

once said conformable material has adhered to said second support, pulling said second support with said conformable material adhered thereto, away from said first support, to leave a patterned area that is based on said surface relief pattern, and to leave said first support.

- 4. (New) A method as in claim 3, wherein said conformable material includes an elastomer.
- 5. (New) A method as in claim 3, further comprising etching indented areas which are formed by contact with said surface relief areas, said etching continuing until said indented areas extend through to said second support.
- 6. (New) A method as in claim 3, wherein said second support is porous, and further comprising initially blocking pores prior to said pressing of said second support, and unblocking the blocked pores after said pulling.
- 7. A method of making a supported mask, comprising:
 obtaining a support;
 applying at least one layer of dielectric material to said support; and
 exposing said layer to patterned light to substantially remove said layer from
 said support in exposed areas

